INFORMATION DISCLOSURE CITATION PTO-1449 Atty. Docket No. 010819 Serial No. 09/891,511

Applicant: Mamoru NAKASUJI et al.

Filing Date: June 27, 2001 Group Art Unit: 2812

U.S. PATENT DOCUMENTS

Examiner Initial P &		Document No.	Name	Date	Class	Subclass	Filing Date (If appropriate)
10	A B	6,125,522	Nakasuji	10/03/00			11/12/96
1 8 2	WAX:	6,087,667	Nakasuji et al.	07/11/00			09/30/97
PACEN	A SE	5,994,704	Nakasuji	11/30/99			10/03/97
MAGEN	AZ	5,981,947	Nakasuji etal.	11/09/99			02/03/98
910	ВА	5,892,224	Nakasuji	04/06/99			05/09/97
910	BC	5,770,863	Nakasuji	06/23/98			10/24/96
910	BD	5,763,893	Nakasuji	06/09/98			12/16/96
18	BE	5,751,538	Nakasuji	05/12/98			09/26/96
gi	BF	5,747,819	Nakasuji et al.	05/05/98			10/30/96
910	BG	5,362,968	Miyoshi et al.	11/08/94			09/27/93
910	ВН	5,359,197	Komatsu et al.	10/25/94			07/16/93
JAB .	BI	4,912,052	Miyoshi et al.	03/27/90			09/23/88

OTHER DOCUMENTS

JB GB	ВЈ	Low Voltage and high speed operating electrostatic wafer chuck using sputtered tantalum oxide membrane, Mamoru Nakasuji et al., J. Vac. Sci. Technol. A 12(5), Sep/Oct 1994, American Vacuum Society pp. 2834-2839.
AP.	вк	High -Emittance and Low-Brightness Electron Gun for Reducing-Image Projection System: Computer Simulation, Mamoru Nakasuji et al., Jpn. J. Appl. Phys. Vol. 36 (1997) pp.2404-2408.
	BL	H. Hayashi, et al., LSI Testing Symposium 1998, Minutes of the meeting, P160 (1998) (partial translation)

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FOREIGN PATENT DOCUMENTS

Group Art Unit: 2812

						
	0112	8	Document No.	Date	Country	Translation (Yes or No)
BATES	JAN B BOOK	Q Q AA	52-115161	09/27/77	JAPAN	ABSTRACT
V	ALLES STATES	AB	52-117567	10/03/77	JAPAN	ABSTRACT
	9/3	AC	57-072326	05/06/82	JAPAN	ABSTRACT
	910	AD	57-125871	08/05/82	JAPAN	ABSTRACT
	1910	AE	60-000741	01/05/85	JAPAN	ABSTRACT
ļ	3/0	AF	62-195838	08/28/87	JAPAN	ABSTRACT
	119	AG	03-022339	01/30/91	JAPAN	ABSTRACT
	913	AH	03-053439	03/07/91	JAPAN	ABSTRACT
	910	AI	03-102814	04/30/91	JAPAN	ABSTRACT
	910	AJ	03-266350	11/27/91	JAPAN	ABSTRACT
	GB.	AK	03-276548	12/06/91	JAPAN	ABSTRACT
	610	AL	04-266350	09/22/92	JAPAN	ABSTRACT
	110	AM	05-063261	03/12/93	JAPAN	ABSTRACT
	910	AN	05-251316	09/28/93	JAPAN	ABSTRACT
	910	AO	07-065766	03/10/95	JAPAN	ABSTRACT
ŀ	910	AP	08-138611	05/31/96	JAPAN	ABSTRACT
	JID -	AQ	09-311112	12/02/97	JAPAN	ABSTRACT
	910	AR	10-062503	03/06/98	JAPAN	ABSTRACT
	999	AS	10-177952	06/30/98	JAPAN	ABSTRACT
	113	AT	11-132975	05/21/99	JAPAN	ABSTRACT
	10	AU	2000-090868	03/31/00	JAPAN	ABSTRACT
	10	AV	07-249393	09/26/95	JAPAN	ABSTRACT

Examiner

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Date Considered

9/25/03

Examiner	Date Considered	
INFORMATION	Atty. Docket No. 010819	Serial No. 09/891,511
DISCLOSURE CITATION	Applicant: Mamoru NAKASUJI et al.	
PTO-1449	Filing Date: June 27, 2001	Group Art Unit:

, ...,

1	OIPE	7	OTHER DOCUMENTS		
FAITE	JAN 1 8 2002	ў Эвм	Multi-Beam Concepts for Nanometer Devices, B. Lischke et al., Japanese Journal of Applied Physics, Vol. 28, No.10, October 1989, pp. 2058-2064.		
	-9B	BN	An electron-beam inspecting system for x-ray mask production, P. Sandland et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec. 1991, American Vacuum Society, pp.3005-3009.		
	BO Requirements and performance of an electron-beam column designed for x-ray mask inspection, W.D. Meisburger et al., J. Vac. Sci. Technol. B9 (6), Nov/Dec 1991, American Vacuum Society, pp.3010-3014.				
	JB	ВР	Table 5-1 Work Function in Metals page 116.		
		BQ			
		BR			
		BS			
	Examiner	suk	Berman Date Considered 9/25/03		

INFORMATION DISCLOSURE CITATION PTO 4459 Atty. Docket No. 010819 Serial No. 09/891,511

Applicant(s): NAKASUJI, et al.

Filing Date: June 27, 2001 Group Art Unit: 2812

U.S. PATENT DOCUMENTS

Examiner Initial	CENT 3 TR	Document No.	Name .	Date	Class	Subclass	Filing Date (If appropriate)
213	AA	4,944,645	Suzuki	7/31/90			_
<i></i>	AB						
	AC						

FOREIGN PATENT DOCUMENTS

		Document No.	Date	Country	Translation (Yes or No)
975	AD	JP 2000-67798 A	03/03/2000	Japan	Abstract only
910	AE	JP 9-73872 A	03/18/1997	Japan	Abstract only
90	АF	JP 63-6737 A	01/12/1988	Japan	Abstract only
413	AG	JP 2000-100369 A	04/07/2000	Japan	Abstract only
110	АH	JP 2000-3692 A	01/07/2000	Japan	Abstract only
912	ΑI	JP 2000-133565 A	05/12/2000	Japan	Abstract only
200	AJ	JP 62-100936 A	05/11/1987	Japan	Abstract only
9/2	AK	JP 10-125271 A	05/15/1998	Japan	Abstract only
2013	AL	JP 11-233062 A	08/27/1999	Japan	Abstract only

/		OTHER DOCUMENTS	TECH
	АМ		RECEI FEB 12
	AN		TVED 200 Enter 2000
Examiner	ack	Berman Date Considered 9/25/03	